EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	38	(wafer or semiconductor or substrate) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and rotate and angle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/24 10:05
S2	1	(wafer or semiconductor or substrate) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and rotate and angle and integer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 09:44
S3	32	(wafer or semiconductor or substrate) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and rotate and angle and degree	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 09:44
S4	18	(wafer or semiconductor or substrate) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and rotate and angle and degree and cycle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 09:46
S5	25	(rotat\$4 near8 (wafer or semiconductor or substrate)) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and angle and degree and cycle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 09:47
S7	8	(rotat\$4 near (wafer or semiconductor or substrate)) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and angle and degree and cycle	USIPGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 09:48

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S8	23	(rotat\$4 near4 (wafer or semiconductor or substrate)) and deposition and (CVD or APCVD or PECVD or HDPCVD) and "thin film" and "deposition system" and gas and (ouput or outlet) and time and angle and degree and cycle	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:24
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